Free-Charge Carrier Properties of Graphene Layers on SiC

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Epitaxial Graphene for THz Electronics **Our Message** · A rotating analyzer-type ellipsometer employing a frequency-tunable Epitaxial Graphene on SiC Substrates Wafer-Scale THz Field-Effect Transistor Dirac Particle Properties backward wave oscillator source was used for Mueller matrix measurements in the THz frequency range. • High mobility few layer graphene (d~1 nm) is observed as a distinct damping of Fabry-Pérot interferences originating from the SiC substrate. The combination of THz and MIR ellipsometry allows the identification of high and low mobility graphene layers grown on C-face SiC few graphene layers are formed on the Si-· Infrared transmission spectroscopy of epitaxia 50 mm graphene wafer was processed by · THz optical-Hall effect data are successfully used for the determination of terminated face (top), with substantially more on standard lithographic techniques graphene revealing Landau level structure the free electron effective mass in epitaxial graphene. the C-terminated face (bottom) absorption maxima positions as a function of field · Graphene based field-effect transistors have been electron doped effects due to the interface electric is characteristic for a chiral "massless" Dirac demonstrated to operate in the 100 GHz range • THz ellipsometry is found to be a very useful tool for the investigation of the field close to the SiC interface particle electrical properties of epitaxial graphene deposited on SiC substrates. P.N. First et al. MRS Bull 35 296-305 (2010) W A de Heer et al. Solid State Commun 143 92 (2007) P. N. First et al. MRS Bull 35 296-305 (2010) **THz Optical-Hall Effect THz Ellipsometry Setup** THz and MIR Ellipsometry C-Face (000-1) Si-Face (0001 polarizer (P) sample (S) rotating analyzer AFM topography of (A) configuration graphene on C-face, $\phi_{n}=80^{\circ}$ Golav detector (GC) (000-1) showing typical "giraffe Backward wave oscillator (BWO) source: AFM topography of Non-zero Muelle nattern graphene on Si-face, matrix M12 22 difference 14 M spectra for δB =3.4 T in C-Face (showing step / W S the THz region allow Achromatic (THz-MIR) polarization bunches the determination of state rotator the graphene free-Facilitates universal use of linea charge carrier effective source polarization mass TEM micrograph φ.=80 application filed with UNL, Sept. 2008 (0001) showing graphen over a step bunch 0.8 0.8 v [THz] 0.9 1.0 vITH₂1 · morphology, growth rate, and roughness Backward wave oscillator (BWO) source: Face are different between C- and Si-face nt Optical-Hall Effect: C-Eace Grown Graph - base resonator frequency 107 to 177 GHz, · graphene on Si-face has transition layer, bandwidth 2 MHz (!), peak power 0.1-0.01 graphene on C-face does not for a given sheet charge density, mobility = 910 GH 0.05 - linearly polarized light S MA of EG on Si-face less than EG on C-face /= 860 G - full spectral range (with Schottky diode multipliers): 0.1 to 1.5 THz = 885 GH 0.0 w. **MIR Ellipsometry** THz Ellipsometry v = 885 GH .0.05 Sample Preparation $\dot{\Phi}_a = 55^\circ$ Φa=80 8 Ma = 910 GH -0.2 50 - 860 GH 68= 3.66 T -0.1 Sublimation of Si from SiC substrates at temperatures >1200°C results in the formation of -0.4 0.8 0.9 10 40 epitaxial graphene at the SiC interface. v[THz] δBIT C-fac M [deg] 30 0.6-0.6 · step bunching results in bi-layer formation on Si-face à, OHE at THz frequencies allows determination $a 6\sqrt{3} \times 6\sqrt{3} R30^\circ$ reconstructed surface of graphene effective mass consistent with 20 6H SiC · low sheet charge density, mobility graphene -0.8 Shubnikov-de Haas measurements on exfoliated graphene 10 · Simultaneous analysis of THz and MIR data The morphology, growth rate, and roughness of -10 C-face epitaxial graphene are different between requires two laver model for graphene (low and high mobility) C- and Si-face 0.8 0.9 600 1000 0.7 1.0 800 1200 C-Face graphene shows a field dependence v ITHz1 ω [cm⁻¹] of effective mass: ted graphen · high sheet charge density, mobility graphene Fabry-Pérot interferences (arrows)

Fingerprint of graphene at the rest-

C-face grown graphene

stahlenband of SiC - more dominant for

originating from the SiC substrate are

damped out for C-face grown graphene

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mobility

graphene layer is covered with "graphitic"

layers with lower carrier concentration and

W (!)

6H SIC

N_s[cm⁻¹]

 $m^*(B) = m_a - m_b \sqrt{B}$

m_a=0.18 and m_b=0.07 for *b*B<3.7T

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